



Demonstration of Record-High mm-Wave Power Performance using N-Polar Gallium Nitride HEMTs

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Outline



- I. Introduction
 - Why GaN?
 - mm-Wave Application Space
 - Status of Competing Device Technologies
 - Demonstrated Advantage of N-Polar GaN
- II. The N-Polar GaN Deep Recess HEMT
 - N-polar vs. Ga-polar GaN HEMTs
 - Enabling Features of the Device Structure
- III. Experimental Results: Large Signal Performance
 - W-Band Device Performance (94 GHz)
 - Ka-Band Device Performance (30 GHz)
- IV. Summary

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Why use GaN? Exceptional Performance for Multiple Applications





mm-Wave Applications





Atmospheric absorption windows and attenuation peaks useful for a variety communication and sensing of applications



79 GHz: Automotive Radar / Collision Avoidance







GaN provides highest output power from 1 to 100 GHz

Qorvo TGA2575 3W **GaAs** Ka-Band PA 5.4 x 4.1mm



5% More Efficient

Qorvo TGA2594 5W **GaN** Ka-Band PA 1.74 x 3.24 mm





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N-Polar breaks through P_{out} saturation observed for traditional Ga-polar devices with **8 W/mm**

Romanczyk et al., IEEE Trans. Electron Devices. Jan. 2018

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GaN HEMT: Polarization Doping





 $\begin{array}{c} -Q_{\pi,AIGaN} \\ +Q_{\pi,AIGaN} \\ \\ -Q_{\pi,GaN} \\ \\ \\ +Q_{\pi,GaN} \\ \end{array}$





Wurtzite Crystal Structure

• Strongly polar in [0001] and [000-1] directions

Polarization is a function of Alloy Composition (Al_xGa_yIn_zN)

 $Q_{\pi,AIGaN} > Q_{\pi,GaN}$

High density (>10¹³ cm⁻²) Channel formed **without impurity doping**

High Mobility & Channel Conductivity

N-Polar vs. Ga-Polar GaN: Inverted Polarization Fields





The N-Polar GaN Deep Recess HEMT Structure





N-Polar Deep Recess Structure

- AIGaN backbarrier provides charge and 2deg confinement
- ✓ Low resistance regrown n⁺ contacts by MBE
- ✓ AIGaN cap & MOCVD SiN Gate Dielectric for low gate leakage
- ✓ GaN Cap for dispersion control and low access resistance
- ✓ Self-aligned gate for process control and low dispersion



N-Polar Deep Recess Design: The GaN Cap





Features of the GaN Cap in Access Regions

- Polarization increases n_s and improves μ_n
 - Enhanced Conductivity: improves Gain & Power
 - Dispersion Control
- In-Situ Growth
- Highly selective recess etch: process well controlled









Polarization also reduces |E| in the GaN channel ⇒ improves mobility

- Channel conductivity improved over wide current range
- Necessary for low V_{knee}

mm-Wave Challenge: Controlling DC-RF Dispersion





Surface states exist in GaN devices

Charge state responds to DC bias



P_{out} and Drain Efficiency are degraded relative to results expected from DC data

Traditional Solutions to Dispersion





SiN passivates surface states & moves external surface far from channel

SiN + Field Plates

Reduced electric field prevent trap ionization

Capacitance penalty disallows use at mm-wave frequencies

$$V_{T,access} = \frac{qn_s}{C}$$

GaN Cap Advantage #2: Dispersion Control







- Increased n_s outweighs differential in ε_r
 ⇒ Higher V_T possible for same capacitance
- 47.5 nm GaN cap: V_{T,access} ≈ 17 V



Sub-10% dispersion thru 16 V V_{DS,Q}

Romanczyk et al. IEEE Trans. Electron Devices. Jan. 2018

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N-Polar GaN Deep Recess Device Overview





Off-State Breakdown: 38 V

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Romanczyk et al. IEEE Trans. Electron Devices. Jan. 2018

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N-Polar GaN: Record W-Band Performance







N-Polar offers greater current density giving higher P_{out}

Record-high combination of PAE and Power Density

Romanczyk et al., IEEE Trans. Electron Devices. Jan. 2018

Constant 8 W/mm: 10 – 94 GHz





- 94 GHz: UCSB Passive Load pull
- 30 GHz: Maury Microwave MT2000 Active Load pull
- 10 GHz: UCSB Passive Load pull

First Demonstration of Constant P_{out} from 10 – 94 GHz

(as expected from ideal FET operation)

Romanczyk et al. IEEE Trans. Electron Devices. Jan. 2018

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Ka-Band Performance (30GHz)





At 30 GHz increased gain allows access to deeper Class AB operation

Romanczyk et al, GOMACTech 2018

Ka-Band Load Pull of GaN Devices





N-Polar offers greater current density

Record-high combination of PAE and Power Density

Romanczyk et al, GOMACTech 2018



N-polar Deep Recess HEMT Advantage

- Inverted polarization fields enable the Deep Recess HEMT design
 - ✓ Enhanced Access Region Conductivity
 - ✓ Control of DC-RF Dispersion

– Large-Signal Performance

- Frequency-Independent P_{out}
- 94GHz:
 - ✓ Record 8 W/mm P_{out}: 4x improvement over traditional Ga-Polar GaN HEMTs
 - ✓ Recond 28.8% Peak PAE

• 30GHz:

- ✓ Record High GaN PAE: 59.8%
- ✓ Record high combinations of PAE and P_{out}
- ✓ 11 dB OIP₃/P_{DC}